

Vapor Phase Decomposition Inductively Coupled Plasma Mass Spectrometry (VPD-ICP-MS)



Vapor Phase Decomposition
Inductively Coupled Plasma
Mass Spectrometry
(VPD-ICP-MS)

Instruments

- Agilent 4500 ICP-MS (all wafer sizes or parts of wafers)

Applications

- Whole wafer analysis with detection limits down to $E07$ atoms/cm²
- Correlation with TXRF measurements

Technical Specifications

- Detection limits down to $E07$ atoms/cm²

For information or to arrange a demonstration please contact the New Pioneers in Surface Analysis Technology:

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